

ABSTRACT

A spin-rinse-dryer (SRD) includes a substrate support adapted to hold and rotate a substrate, and a source of fluid adapted to supply fluid to the surface of a substrate positioned on the substrate support. The SRD also includes at least one shield positioned to receive fluid displaced from a substrate rotating on the substrate support. The shield includes a substrate-facing surface that has been particle-blasted to cause the substrate-facing surface to have a hydrophilic characteristic.